

SEMICONDUCTOR INTRA-FIELD DOSE CORRECTION

Abstract of the Disclosure

A system and method are provided for automatic dose-correction
5 recipe generation, the system including a dose-correction recipe
generator, a reticle data unit in signal communication with the recipe
generator, a slit data unit in signal communication with the recipe
generator, a process data unit in signal communication with the recipe
generator, a wafer data unit in signal communication with the recipe
10 generator, a control unit in signal communication with the recipe
generator, and an output unit or a storage unit in signal communication
with the control unit; and the method including receiving a current reticle
data set and a previous reticle data set, receiving a current slit data set
and a previous slit data set, receiving a process condition, receiving a
15 wafer condition, automatically generating a dose-correction recipe in
accordance with the received reticle, slit, process and wafer information,
and controlling a dose in accordance with the generated recipe.

Fig. 6